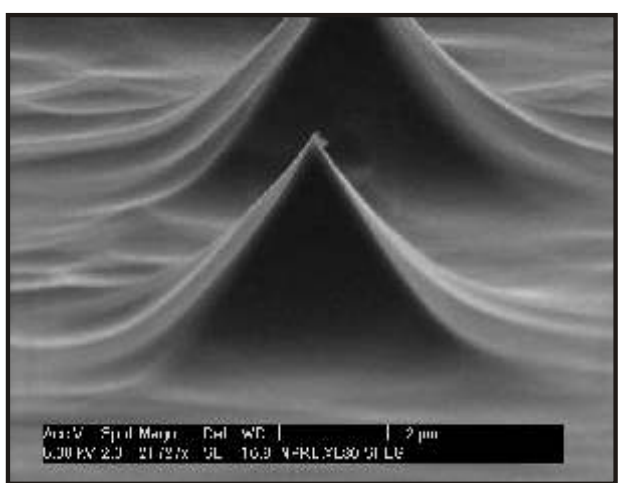
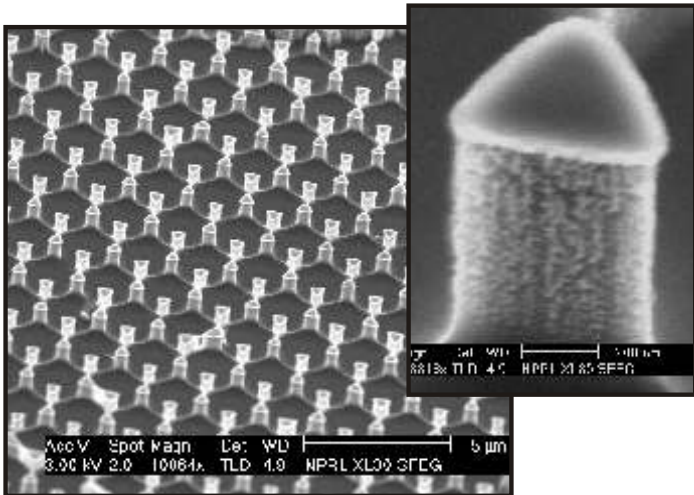
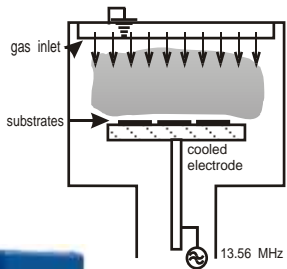
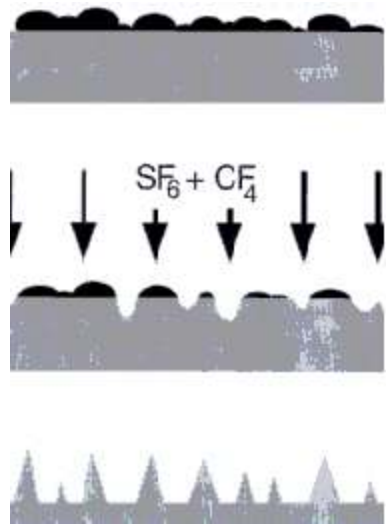


Plasmalab Data

Si cones and pillars dry etching (RIE)

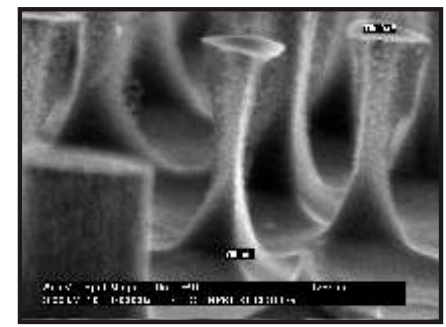


Si nanopillars: The mask is Cr sputter deposited through a polystyrene sphere raft.



Silicon pyramids: These were masked with a photoprocess-able polyimide.

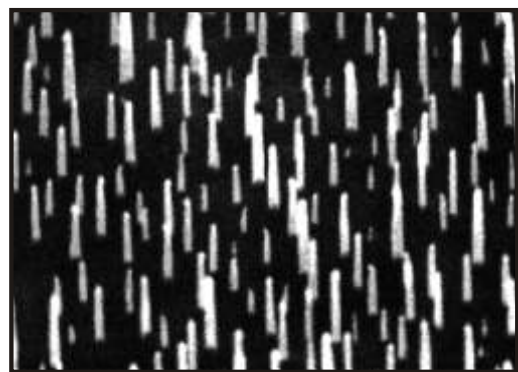
Parallel Plate Configuration
 RIE Mode (13.56 Mhz)
 F based process



Si nanopillars:
 Cr mask, etched more than once



Courtesy of
 Dr Parker
 Dr Seeger
 Prof Palmer
 Nanoscale Physics
 Research Laboratory
 The School of Physics
 & Astronomy
 The University
 of Birmingham



Si nanopillars at 5 - 20 nm diameter
 using a sputtered Ag mask

Angle distribution
 of the Si cones in
 dependence
 of the applied
 RIE power

- Plasmalab 80 Plus*
- Plasmalab 800 Plus*
- Plasmalab System 100*
- Plasmalab System 133*

